Sheet 1 of 2

INVENTOR US 10-1449 (REV. 1/06)	US Dept. of Commerce PATENT & TRADEMARK OFFICE	ATTY DOCKET NO. 125473	APPLICATION NO. 10/551,130
		APPLICANT Takahiro KISHIOKA	
		FILING DATE September 29, 2005	GROUP 1756

U.S. PATENT DOCUMENTS

Examiner Initials	Cite No.	Document Number	Date	Name
CH	1	US 5,919,599	7/6/1999	Meador et al.
CH	2	US 5,693,691	12/2/1997	Flaim et al.
CH	3	US 6,114,085	9/5/2000	Padmanaban et al.
CH	4	US 6,388,039 B1	5/14/2002	Jung et al.
CH	5	US 6,492,092 B1	12/10/2002	Foster et al.
CH	6	US 2002/0093069 A1	7/18/2002	Hong et al.
CH	7	US 2002/0127789 A1	9/12/2002	Hong et al.
CH	8	US 2002/0009595 A1	1/24/2002	Hong et al.

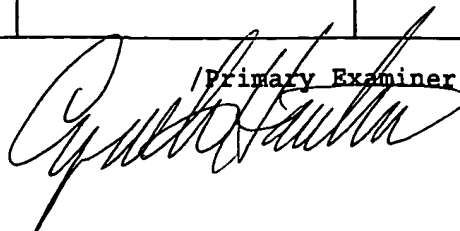
FOREIGN PATENT DOCUMENTS

Examiner Initials	Cite No.	Document Number	Date	Country	With English Abstract	With English Translation
CH	9	JP A 2000-294504	10/20/2000	Japan	X	X
CH	10	JP A 2002-47430	2/12/2002	Japan	X	X
CH	11	JP A 2002-190519	7/5/2002	Japan	X	X
CH	12	WO 02/05035 A1	1/17/2002	WIPO	X	
CH	13	JP A 2002-128847	5/9/2002	Japan	X	X
CH	14	JA A 11-279523	10/12/1999	Japan	X	X
CH	15	WO 02/086624 A1	10/31/2002	WIPO	X	
CH	16	JP A 2002-530696	9/17/2002	Japan	X	X
CH	17	JP A 2001-49231	2/20/2001	Japan	X	X
CH	18	JP A 2002-539282	11/19/2002	Japan	X	X
CH	19	JP A 10-333336	12/18/1998	Japan	X	X
CH	20	JP A 2002-105137	4/10/2002	Japan	X	X
CH	21	JP A 6-35201	2/10/1994	Japan	X	X
CH	22	JP A 2002-97231	4/2/2002	Japan	X	X
CH	23	JP A 2001-194799	7/19/2001	Japan	X	X
CH	24	JP A 10-120939	5/12/1998	Japan	X	X
CH	25	JP A 6-118656	4/28/1994	Japan	X	X

Date: May 11, 2006

/Primary Examiner Cynthia Hamilton/

09/21/2006


9/2/06



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Form PTO-1449 (REV. 1/06)		US Dept. of Commerce PATENT & TRADEMARK OFFICE		ATTY DOCKET NO. 125473	APPLICATION NO. 10/551,130
INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)				APPLICANT Takahiro KISHIOKA	
				FILING DATE September 29, 2005	GROUP 1756
OTHER DOCUMENTS					
Examiner Initials	Cite No.	(Including Author, Title, Date, Pertinent Pages, etc.)			
CH	26	Lynch et al.; "Properties and Performance of Near UV Reflectivity Control Layers;" Proceedings of SPIE, 1994, Vol. 2195, pp. 225-229.			
CH	27	Taylor et al.; "Methacrylate Resists and Antireflective Coatings for 193 nm Lithography;" Proceedings of SPIE, March 1999, Vol. 3678, pp. 174-185.			
CH	28	Meador et al.; "Recent Progress in 193 nm Antireflective Coatings;" Proceedings of SPIE, March 1999, Vol 3678, pp. 800-809.			
EXAMINER	/Primary Examiner Cynthia Hamilton/				DATE CONSIDERED 09/21/2006
Examiner:	Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.				

9/21/2006